

ABSTRACT OF THE DISCLOSURE

A method and system to form a refractory metal layer on a substrate features

10 nucleating a substrate using sequential deposition techniques in which the substrate is serially exposed to first and second reactive gases followed by forming a layer, employing vapor deposition, to subject the nucleation layer to a bulk deposition of a compound contained in one of the first and second reactive gases.

Figure 1: A schematic diagram of the proposed system. The system consists of a user, a server, and a database. The user sends a request to the server, which then queries the database. The database returns the results to the server, which then sends them back to the user. The server also stores the results in the database.